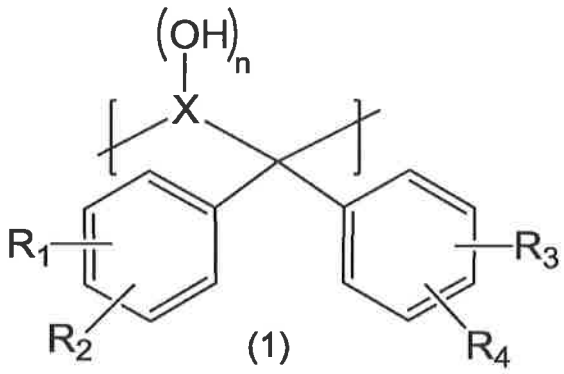
CLAIMS

1. A resist underlayer film-forming composition comprising a polymer having a structural unit of the following Formula (1):



(wherein X is an arylene group, n is 1 or 2, and R_1, R_2, R_3, and R_4 are each independently a hydrogen atom, a hydroxy group, a C_{1-3} alkyl group, or a phenyl group), and a solvent.

2. The resist underlayer film-forming composition according to claim 1, wherein the arylene group is a phenylene group or a naphthylene group.

3. The resist underlayer film-forming composition according to claim 1 or 2, further comprising a crosslinker.

4. The resist underlayer film-forming composition according to claim 3, further comprising an acidic compound of promoting a cross-linking reaction.

5. The resist underlayer film-forming composition according to any one of claims 1 to 4, further comprising a surfactant.